

	Hits	Search Text	DBs
3	2	((resist or photoresist or photosensitive) same develop\$4 smae (wafer or holder or substrate) same (rotat\$4 or spin\$5) same (surfactant or hydrphilic\$5 or hydrophob\$5 or (surface near9 (modification or modify\$4 or active) near9 agent))) and (surfactant same (resist or photoresist) same (expos\$4 or illuminat\$4 or irradiat\$4) same (hold\$3 or stage or chuck) same (rotat\$5 or spin\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	5	((resist or photoresist or photosensitive) same develop\$4 smae (wafer or holder or substrate) same (rotat\$4 or spin\$5) same (surfactant or hydrophilic\$5 or hydrophob\$5 or (surface near9 (modification or modify\$4 or active) near9 agent))) and ((surfactant or (defect near5 preven\$5 near9 agent) or (surface near9 (modifying or modification))) same (resist or photoresist) same (expos\$4 or illuminat\$4 or irradiat\$4) same (hold\$3 or stage or chuck) same (rotat\$5 or spin\$5))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	11	((resist or photoresist or photosensitive) same develop\$4 same (wafer or holder or substrate) same (expos\$4 or illuminat\$4 or irradiat\$4) same (rotat\$4 or spin\$5) same (surfactant or hydrophilic\$5 or hydrophob\$5 or (surface near9 (modification or modify\$4 or active) near9 agent))) and ((surfactant or (defect near5 preven\$5 near9 agent) or (surface near9 (modifying or modification))) same (resist or photoresist) same (hold\$3 or stage or chuck or mount\$4) same (rotat\$5 or spin\$5) same (dry\$3 or heat\$3 or bak\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	4	((resist or photoresist or photosensitive) same develop\$4 same (wafer or holder or substrate) same (expos\$4 or illuminat\$4 or irradiat\$4) same (rotat\$4 or spin\$5) same (dry\$5 or remov\$4 or rins\$4 or displac\$4 or replac\$4 or uniform\$5 or strip\$5)) and ((surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near12 (modifying or modification or active))) same (resist or photoresist) same (hold\$3 or stage or chuck or mount\$4) same (rotat\$5 or spin\$5) same (dry\$3 or heat\$3 or bak\$4)) and ((wet\$5 or surfactant) same ((contact near16 angle) or hydrophob\$5 or hydrophil\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	6	((resist or photoresist or photosensitive) same develop\$4 same (wafer or holder or substrate) same (expos\$4 or illuminat\$4 or irradiat\$4) same (rotat\$4 or spin\$5) same (dry\$5 or remov\$4 or rins\$4 or displac\$4 or replac\$4 or uniform\$5 or strip\$5)) and ((surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near12 (modifying or modification or active))) same (resist or photoresist) same (hold\$3 or stage or chuck or mount\$4) same (rotat\$5 or spin\$5) same (dry\$3 or heat\$3 or bak\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	16	((resist or photoresist or photosensitive) same develop\$4 same (wafer or holder or substrate) same (expos\$4 or illuminat\$4 or irradiat\$4) same (rotat\$4 or spin\$5) same (dry\$5 or remov\$4 or rins\$4 or displac\$4 or replac\$4 or uniform\$5 or strip\$5)) and ((surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active or treat\$5))) same (resist or photoresist) same (hold\$3 or stage or chuck or mount\$4) same (rotat\$5 or spin\$5) same (dry\$3 or heat\$3 or bak\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	10	((resist or photoresist or photosensitive) same develop\$4 same (wafer or holder or substrate) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((resist or photoresist) same (rotat\$4 or spin\$5) same (dry\$5 or remov\$4 or rins\$4 or displac\$4 or replac\$4 or uniform\$5 or strip\$5) same develop\$6) and ((surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (resist or photoresist) same (hold\$3 or stage or chuck or mount\$4) same (rotat\$5 or spin\$5) same (dry\$3 or heat\$3 or bak\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	1	134/24.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	9	"134"/\$.ccls. and develop\$5 and (nozzle same (shape or geometr\$6) same (band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
12	5	"396"/\$.ccls. and develop\$5 and (nozzle same (shape or geometr\$6) same (band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	153	develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	1	(develop\$5 same nozzle same (shape or geometr\$6) same (band or rectang\$4) same (plural\$5 or multilple)) and (nozzle same (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	2	(develop\$5 same nozzle same (shape or geometr\$6) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4) same (plural\$5 or multilple)) and (nozzle same (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
16	7	(develop\$5 same nozzle same (shape or geometr\$6) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4) same (plural\$5 or multilple)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	1	430/311.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)) and (resist or photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	5	"430"/\$.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent)) and (resist or photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	20	((resist or photoresist or photosensitive) same develop\$4 same (wafer or holder or substrate) same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (resist or photoresist) same (hold\$3 or stage or chuck or mount\$4) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	40	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (vary\$4 or var\$5 or adjust\$\$ or chang\$4 or alter\$4) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	157	((resist or photoresist or photosensitive) same develop\$4 same (expos\$4 or illuminat\$4 or irradiat\$4)) and ((surface\$4active or surfactant or (defect\$5 near12 preven\$5 near12 agent) or (surface near16 (modifying or modification or active))) same (amount or concentration or percentage or percent) same (resist or photoresist) same thickness)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
22	1	396/627.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4)) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	3	396/627.ccls. and develop\$5 and (nozzle same (multiple or pluralit\$4) same (shape or geometr\$6) same (cylindrical or circular or circle or band or rectang\$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	5	(develop\$5 same nozzle same (shape or geometr\$6) same (band or rectang\$4) same (plural\$5 or multilple)) and ((resist or photoresist) same (expos\$4 or illuminant\$4 or irradiat\$4) same develop\$4) and (surface\$4active or (surface near9 (active or modifying or modification or alter\$4)) or surfactant or (defect near6 prevent\$4 near9 agent))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	8	(develop\$5 same nozzle same (shape or geometr\$6) same (band or rectang\$4) same (plural\$5 or multilple)) and ((resist or photoresist) same (expos\$4 or illuminant\$4 or irradiat\$4) same develop\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB